

ABSTRACT

A vacuum arc vapor deposition apparatus includes a plurality of magnetic coils for guiding a plasma produced by a vacuum arc evaporating source to the vicinity of a substrate
5 in a film forming chamber by use of a deflection magnetic field. The vacuum arc vapor deposition apparatus further includes a coil power source for reversing a coil current to be fed to the magnetic coils, and a control unit for controlling the coil
10 ~~power~~ source to reverse the flowing direction of the coil current.